

Form PTO-1449 (modified)	Atty. Docket No. 102-0102US	Serial No. unk
List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)	Inventor/Applicant: Neal R. Rueger / Micron Technology, Inc.	
	Title: IMPROVED INDUCTIVELY COUPLED PLASMA CHAMBER ATTACHABLE TO A PROCESSING CHAMBER FOR ANALYSIS OF PROCESS GASES	
	Filing Date: herewith	Group: unk

U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
	A1						

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
N	C1	Bladimiro Ruiz, Jr. & Herbert E. Litvak, "Investigation of Silicon Trench Etch Chemistry Using a Downstream Chemical Monitor," 4th AVS Int'l Conference on Microelectronics and Interfaces (2003)
N	C2	Freddy Gaboriau et al., "Langmuir Probe Measurements in an Inductively Coupled Plasma: . . .," J. Vac. Sci. Technol., Vol. A20(3), pp. 919-27 (May/Jun 2002);
N	C3	M.V. Malyshev et al., "Diagnostic Studies of Aluminum Etching in an Inductively Coupled Plasma System: . . .," J. Vac. Sci. Technol., Vol. A18(3), pp. 849-59 (May/Jun 2000)
N	C4	D.M. Manos et al., "Characterization of Laboratory Plasmas With Probes," J. Vac. Sci. Technol., Vol. A3(3), pp. 1059-66 (May/Jun 1985)
N	C5	S.M. Rossnagel et al., "Langmuir Probe Characterization of Magnetron Operation," J. Vac. Sci. Technol., Vol. A4(3), pp. 1822-25 (May/Jun 1986)
N	C6	V. Kaepelin et al., "Ion Energy Distribution Functions and Langmuir Probe Measurements in Low Pressure Argon Discharges," J. Vac. Sci. Technol., Vol. A20(2), pp. 526-29 (Mar/Apr 2002)
N	C7	Terry A. Miller, "Optical Emission and Laser-Induced Fluorescence Diagnostics," J. Vac. Sci. Technol., Vol. A4(3), pp. 1768-72 (May/Jun 1986)

EXAMINER: <u>Rueger</u>	DATE CONSIDERED: <u>6/9/06</u>
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Exam. Init.	Ref. Des.	Citation
N	C8	V.M. Donnelly, "A Simple Optical Emission Method for Measuring Percent Dissociations of Feed Gases in Plasmas: . . .," J. Vac. Sci. Technol., Vol. A14(3), pp. 1076-87 (May/Jun 1996)
N	C9	A.D. Kuypers et al., "Emission Spectroscopy and Actinometry in a Magnetized Low Pressure Radio Frequency Discharge," J. Vac. Sci. Technol., Vol. A8(5), pp. 3736-45 (Sep/Oct 1990)
N	C10	Zhimin Wan et al., "Electron Cyclotron Resonance Plasma Reactor for SiO ₂ Etching: . . .," J. Vac. Sci. Technol., Vol. A13(4), pp. 2035-43 (Jul/Aug 1995)
	C11	

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